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## LIST OF PATENTS AND PUBLICATIONS FOR APPLICANT'S INFORMATION DISCLOSURE STATEMENT

ATTY. DOCKET NO.: P69084USO GROUP ART UNIT: Not Yet Assigned  
SERIAL NO.: Not Yet Assigned FILING DATE: August 22, 2003  
APPLICANT(S): Jung Wook LIM, et al. TODAY'S DATE: August 22, 2003

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## U.S. PATENT DOCUMENTS

EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	INT'L CLASS	SUB- CLASS	FILING DATE (if Appropriate)
<u>Ac</u>	AA 6,416,822	7/09/02	Chiang, et al.	B05D	3/00	3/19/01
<u>Ac</u>	AB 6,468,924	10/22/02	Lee, et al.	H01L	21/31	5/31/01

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## FOREIGN PATENT DOCUMENTS

EXAMINER INITIAL	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUB- CLASS	TRANSLATION (YES) (NO)
<u>Ac</u>	AC 2002-46431	06/21/02	KOREA (ROK)	H01L	29/108	X
	AD					
	AE					

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## OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)

Ac AF Jin-Seong Park, et al.; "Plasma-Enhanced Atomic Layer Deposition of Ta-N Thin Films"; Journal of The Electrochemical Society, 149 (1) C28-C32 (2002).

Ac AG Hyun-Jung Song, et al.; "Increment of the Dielectric Constant of Ta<sub>2</sub>O<sub>5</sub> Thin Films by Retarding Interface Oxide Growth on Si Substrates"; Electrochemica and Solid-State Letters, 4(7) F13-F14 (2001).

EXAMINER

DATE CONSIDERED

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant(s).